



# Fully Automatic Grinder/Polisher

## **Ultra-Thin Grinding and Stress Relief Combined**



DGP8760 unifies 300 mm wafer grinding and advanced stress relief options in one low-footprint system.

#### **Advanced 3-Spindle 4-Chuck Design**

Featuring 3 spindles, DGP8760 combines ultra-thin grinding and stress relief into one complete and uninterrupted process. By keeping each wafer on the same chuck table from start to finish, the efficient turntable-based design minimizes wafer handling and increases process stability for 50  $\mu$ m finishing and other vanguard applications.

#### **Reduced Footprint**

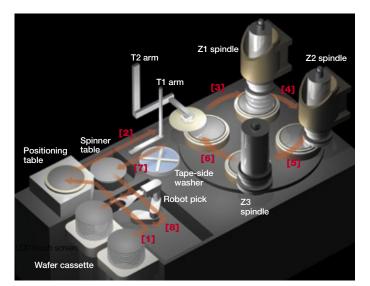
Owing to its 3-spindle 4-chuck design and compact wafer transfer system, DPG8760's footprint is more than 36% smaller than that of DFG8560 and DFP8160 combined. Additionally, the vacuum unit is completely contained within the machine case for extra compactness.





ISO 9001 REGISTERED ORGANIZATION No. E892 - ISO 14001





#### **DGP8760 Workpiece Flow System**

[1] The robot pick removes the wafer from the cassette and places on the positioning table, where centering takes place.

- [2] The T1 arm places the wafer on the chuck table.
- [3] The wafer proceeds to Z1 for rough grinding.
- [4] The wafer proceeds to Z2 for fine grinding.
- [5] The wafer proceeds to Z3 for dry polishing (or ultra-high-mesh wheel grinding).
- [6] The T2 arm removes the wafer from the chuck table and places it on the spinner table, where washing and drying take place.
- [8] Finally, the robot pick removes the wafer from the spinner table and places it in the cassette.

#### **Robust Applications Support**

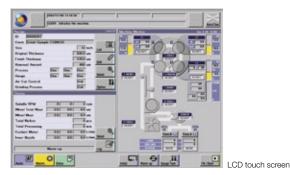
Rough grinding, fine grinding, and stress relief-because it supports all three functions, DGP8760's portfolio of applications is large and robust. Stress relief options include both dry polishing and Poligrind grinding.

#### **In-line Expandability**

DGP8760 can be configured in-line with DFM2700 for DAF lamination and other tape functions. It is also configurable with Disco's DBG (Dicing Before Grinding) system and with a wide variety of other machines: tape mounter, tape remover, etc.

#### **Disco 8000 Series Compatibility**

DGP8760's grinding wheels, polishing wheels, dresser boards, spindles, and chuck tables are all compatible with Disco 8000 Series machines. In addition, operation method and GUI (Graphical User Interface) are based on proven 8000 Series technology.



#### Environmental conditions

- Use clean, oil-free air at a dew point of -15 °C or less. (Use a residual oil: 0.1 ppm. Filtration rating: 0.01 µm/99.5 % or more).
- •Keep room temperature fluctuations within ±1 °C of the set value. (Set value should be between 20 25 °C).
- Keep grinding water and cleaning water 2 °C above room temperature (fluctuations within 1 °C over one hour).
  Keep spindle cooling water temperature between 20 25 °C (fluctuations within 2 °C over an hour).
- The machines should be used in an environment, free from external vibration. Do not install machine near a ventilation opening, heat generation equipment or oil mist generating parts.
- •This machine uses water. In case of water leakage, please install the machine on the floor with sufficient waterproofing and drainage treatments.
- \* All pressures specified above are gauge pressures.
- \* As the above specification may change due to technical modifications. Please confirm when placing your order.
- \* For further information, please contact your local sales representative



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Fully Automatic Grinder/Polisher DGP8760



Wafer Dia	ameter		mm	Max. ø300 (ø8" - ø12")
Grinding	Z1and Z2	axis	-	In-feed grinding with wafer rotation
Method	Z3 axis		-	Anomalous in-feed polishing with wafer rotation
Spindle	Туре		-	Air bearing with high frequency moto
	Number of	faxes	-	3
	Output	Z1 and Z2 axes	kW	4.8
		Z3 axis	kW	7.5
	Revolution	Z1 and Z2 axes	min <sup>-1</sup>	1,000 - 4,000
	speed	Z3 axis	min <sup>-1</sup>	1,000 - 3,000
	7-axis vertical	Z1 and Z2 axes	mm	120 (with zero point)
	stroke	Z3 axis	mm	50
	-		d mm/s	0.0001~0.08
	Z-axis vertical fast feed speed mm/s		50	
	Min. Z-axis vertical movemnet		0.1	
	Min. Z-axis vertical movement resolution $\mu m$			0.1
Wafer	Chuck tab		-	Porous chuck table
Chuck Table	Holding method -			Vacuum
	Number of revolutions min <sup>-1</sup>			0 - 300
	Number of chuck tables -			4
	Chuck table cleaning -			Backflushing of water and compressed air is
	ondok table olea ing			combined with oilstone cleaning and brush cleaning
	Wafer cleaning -			Water washing by atomizing nozzle
	Spark out (chuck table revolutions setting) -			0 - 999
Grinding	Diamond v			ø300
Wheels	Dry polishi		axis mm	ø450
Nafer Han		n/Wafer Cleaning Sec		
		torage quantity	-	2
	Cassette f		-	Same flow and open flow
	Spinner unit -		-	Water washing by atomizing nozzle and dryi
/acuum	Discharge speed	Pump	-	26/34 m <sup>3</sup> /h, 50/60 Hz
		Vacuum Unit	-	20/28 m <sup>3</sup> /h, 50/60 Hz (at -70 kP
	Achievable		kPa	-90 (at water supply temperature 15 °C and flow rate 1 L/r
	Electric mo		kW	1.5
	Water flow rate			2.0 (when water supply temperature is less than 30
			L.	1.5 (when water supply temperature is less than 25
				1.0 (when water supply temperature is less than 20
Grinding	Accuracy (	vhen grinding ø300 mm w	afers with	included chuck tables)
	Thickness variation within one wafer			less than 3.0 (less than 3.0 when using only Z1 and Z
	Thickness variation between wafers µm			$\pm 3.0$ (±3.0 when using only Z1 and Z2)
	Finish surface roughness µm [when using only			Ra less than 0.005
				Z1 and Z2 Ry approx 0.13 (#2000 fine grindin
				Ry approx 0.15 (#1400 fine grindin
Utilities	Power sup	ply	-	200 ~ 240 V AC±10 %, 3-phase (50/60 H
				For other than the above voltages, a transformer is necess
	Power	During processing	kW	8.4 (for reference)
		<sup>n</sup> During warm-up	kW	2.8 (for reference)
	Max. powe		kVA	26
	Air	Main body	MPa	0.6 - 0.8
	Air pressure	Main body Polishing residue collect		0.6 - 0.8 0.3 - 0.5
				0.3 - 0.5 During max. flow: 1,300 or less Average during processing: 700 or le
	pressure Air flow	Polishing residue collect Main body	tor MPa L/min (ANR)	0.3 - 0.5 During max. flow: 1,300 or less Average during processing: 700 or le
	pressure Air flow	Polishing residue collect Main body Polishing residue collector t	tor MPa L/min (ANR) _/min (ANR)	0.3 - 0.5 During max, flow, 1,300 or less Average during processing; 700 or le During warming up; 450 or less 50
	pressure Air flow rate	Polishing residue collect Main body Polishing residue collector Grinding and clean	tor MPa L/min (ANR) _/min (ANR) ing MPa	0.3 - 0.5 During max. flow: 1,300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4
	Air flow rate Water	Polishing residue collect Main body Polishing residue collector L Grinding and clean Cooling water and vaccum p	tor MPa L/min (ANR) _/min (ANR) ing MPa	0.3 - 0.5 During max. flow: 1,300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4 0.2 - 0.3
	Air flow rate Water	Polishing residue collect Main body Polishing residue collector L Grinding and clean Cooling water and vaccum Vacuum pump	tor MPa L/min (ANR) ./min (ANR) ing MPa bump MPa MPa	0.3 - 0.5 During max. flow. 1.300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45
	Air flow rate Water pressure	Polishing residue collect Main body Polishing residue collector u Grinding and clean Cooling water and vaccum Vacuum pump Polishing residue collect	tor MPa Umin (ANR) /min (ANR) ing MPa oump MPa MPa tor MPa	0.3 - 0.5 During max. flow. 1.300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3
	Air flow rate Water	Polishing residue collect Main body Polishing residue collector u Grinding and clean Cooling water and vaccum Vacuum pump Polishing residue collect Grinding and cleani	tor MPa L/min (ANR) ing MPa oump MPa MPa tor MPa ing L/min	0.3 - 0.5 During max. flow: 1.300 or less Average during processing: 700 or le During warming ux: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3 25 or higher
	Air flow rate Water pressure Water	Polishing residue collect Main body Polishing residue collector u Grinding and clean Cooling water and vacum Vacuum pump Polishing residue collect Grinding and cleani Cooling water	tor MPa L/min (ANR) J/min (ANR) ing MPa bump MPa MPa tor MPa ing L/min L/min	0.3 - 0.5 During max, flow: 1,300 or less Average during processing: 700 or le During warming ux: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3 25 or higher 9.5 or higher
	Air flow rate Water pressure Water	Polishing residue collect Main body Polishing residue collector u Grinding and clean Cooling water and vaccum Vacuum pump Polishing residue collect Grinding and cleani	tor MPa L/min (ANR) ing MPa oump MPa MPa tor MPa ing L/min	0.3 - 0.5 During max. flow. 1,300 or less Average during processing. 700 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3 25 or higher 2.0 (when water supply temperature is less than 30 °C
	Air flow rate Water pressure Water	Polishing residue collect Main body Polishing residue collector u Grinding and clean Cooling water and vacum Vacuum pump Polishing residue collect Grinding and cleani Cooling water	tor MPa L/min (ANR) J/min (ANR) ing MPa bump MPa MPa tor MPa ing L/min L/min	0.3 - 0.5 During max. flow. 1.300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3 25 or higher 9.5 or higher 2.0 (when water supply temperature is less than 30 °C 1.5 (when water supply temperature is less than 30 °C
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	Pressure Air flow rate Water pressure Water flow	Polishing residue collect Main body Polishing residue collector of Grinding and clean Cooling water and vaccum Polishing residue collect Grinding and cleani Cooling water Vacuum pump Polishing residue collect Polishing residue collect	tor MPa L/min (ANR) J/min (ANR) ing MPa oump MPa MPa tor MPa I/min L/min L/min tor L/min m <sup>3</sup> /min	0.3 - 0.5 During max. flow: 1.300 or less Average during processing: 700 or le During warming up: 450 or less 50 0.3 - 0.4 0.2 - 0.3 0.05 - 0.45 0.2 - 0.3 25 or higher 9.5 or higher 2.0 (when water supply temperature is less than 30 °C 1.5 (when water supply temperature is less than 20 °C 4

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